	Hits	Search Text	DBs
18	0	((selective$5 or response or signal$4 or (defect near9 portion)) same (sensor or detector or interferometer or microscope or SEM) same (mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post$4heat$4 or heat$4) same (line$3dege$3roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3)) same (pattern or ((resist or photoresist) near9 (structure or pattern$4)))) and (((trim$4 near5 etch$4) or trim$5 or etch$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
19	1	((selective$5 or response or signal$4 or (defect near9 portion)) same (sensor or detector or interferometer or microscope or SEM) same (mitigat$4 or reduc$4 or decreas$4 or monitor$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post$4heat$4 or heat$4) same (line$3dege$3roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3)) same (pattern or ((resist or photoresist) near9 (structure or pattern$4))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	38	S21 NOT S20	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
21	43	((sensor or detector or interferometer or microscope or SEM) same (detect$4 or monitor$4 or respons$4 or sens$5 or observ$5) same (line$4edge$4roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3)) same (pattern or ((resist or photoresist) near9 (structure or pattern$4)))) and ((mitigat$4 or reduc$4 or decreas$4 or chang$4 or alter$4 or correct$4) same (line$4edge$4roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3)) same ((pattern or structure) near12 (resist or photoresist)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
22	13	((sensor or detector or interferometer or microscope or SEM) same (mitigat$4 or reduc$4 or decreas$4 or chang$4 or alter$4 or correct$4) same (detect$4 or monitor$4 or respons$4 or sens$5) same (line$4edge$4roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3)) same (pattern or ((resist or photoresist) near9 (structure or pattern$4))))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
23	1	((sensor or detector or interferometer or microscope or SEM) same (detect$4 or monitor$4 or respons$4 or sens$5 or observ$5) same (line$4edge$4roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3)) same (pattern or ((resist or photoresist) near9 (structure or pattern$4)))) and ((mitigat$4 or reduc$4 or decreas$4 or chang$4 or alter$4 or correct$4) near12 (line$4edge$4roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3)) near16 ((defect near9 portion) or select$5 or portion) near22 ((pattern or structure) near12 (resist or photoresist)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
25	30	((sensor or detector or interferometer or microscope or SEM) same (detect$4 or monitor$4 or respons$4 or sens$5 or observ$5) same (line$4edge$4roughness or ((edge or side$4) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3)) same (pattern or ((resist or photoresist) near9 (structure or pattern$4)))) and ((mitigat$4 or reduc$4 or decreas$4 or chang$4 or alter$4 or correct$4 or smooth$6) near12 (line$4edge$4roughness or ((edge or side$6) near12 roughnes$4) or LER or (line$3 near3 edge near4 roughnes$3)) near22 ((pattern or structure) near12 (resist or photoresist)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB